Fundamentals of Nanotransistors

Unit 2: MOS Electrostatics

Lecture 2.5: Mobile Charge: Bulk MOS

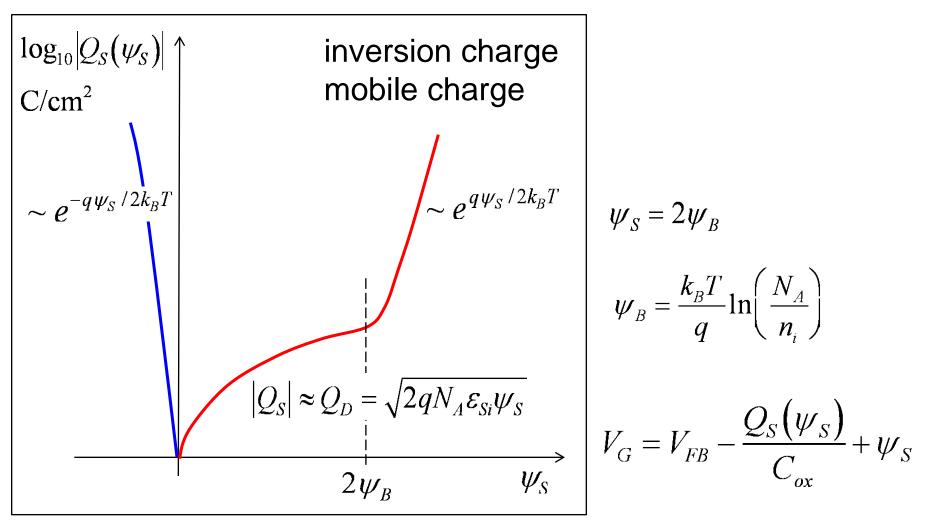
Mark Lundstrom

lundstro@purdue.edu Electrical and Computer Engineering Birck Nanotechnology Center Purdue University, West Lafayette, Indiana USA

Lundstrom: Nanotransistors 2015



Where we are



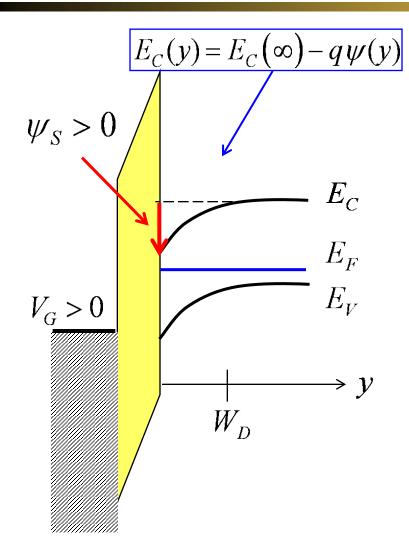
MOSFET drain current

$$I_{DS}/W = -Q_n (V_{GS}) \langle \upsilon (V_{DS}) \rangle$$

We have been discussing Q_s and Q_D , but we need Q_n as a function of surface potential and gate voltage.

$$Q_{S}(\psi_{S}) = Q_{D}(\psi_{S}) + Q_{n}(\psi_{S})$$
$$Q_{S}(V_{G}) = Q_{D}(V_{G}) + Q_{n}(V_{G})$$

Mobile charge (per cm³)



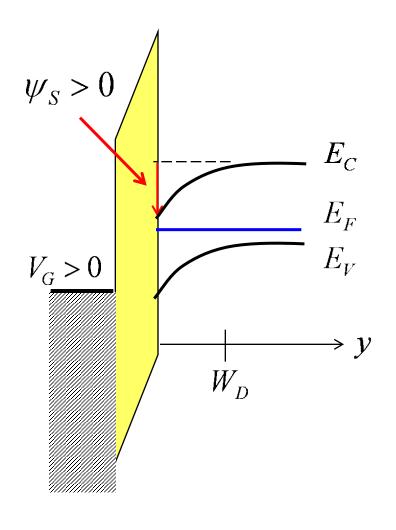
$$Q_n = -q \int_0^\infty n(y) dy = -q n_S \quad \text{C/cm}^2$$

$$n_0(y) = N_C e^{\left(E_F - E_C(y)\right)/k_B T}$$

$$n_0(y) = N_C e^{\left(E_F - E_C(\infty)\right)/k_B T} \times e^{q \psi(y)/k_B T}$$

$$n_0(y) = n_B \times e^{q\psi(y)/k_BT}$$
$$n_B = \frac{n_i^2}{N_A}$$

Mobile sheet charge (per cm²)



$$Q_{n} = -q \int_{0}^{\infty} n(y) dy$$

$$= -q \int_{0}^{\infty} n_{B} e^{q \psi(y)/k_{B}T} dy$$

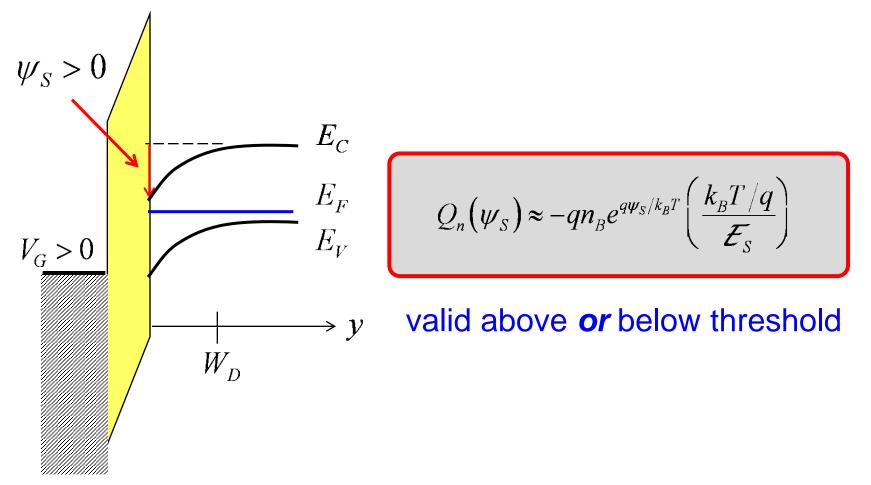
$$= -q n_{B} \int_{0}^{\psi_{S}} e^{q \psi(y)/k_{B}T} \frac{dy}{d\psi} d\psi$$

$$\approx \frac{q n_{B}}{\mathcal{F}_{S}} \int_{0}^{\psi_{S}} e^{q \psi(y)/k_{B}T} d\psi$$

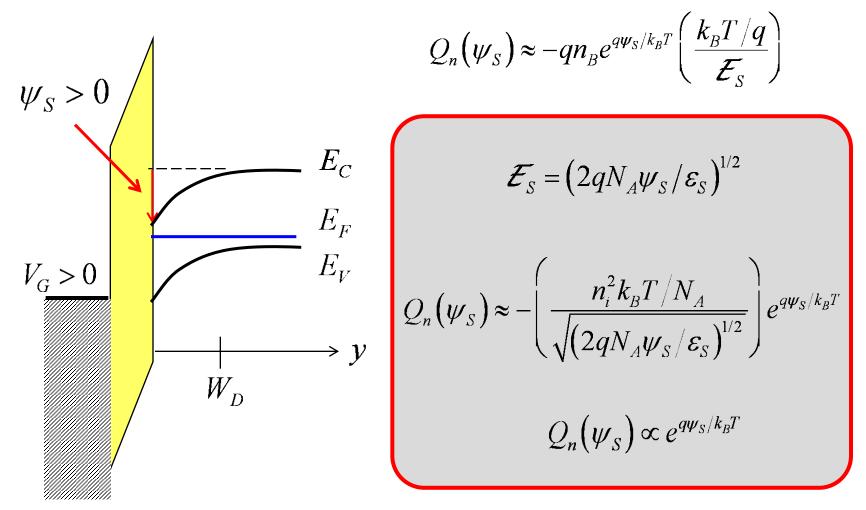
$$Q_{n} \approx -q n_{B} e^{q \psi_{S}/k_{B}T} \left(\frac{k_{B}T/q}{\mathcal{F}_{S}}\right)$$

$$Q_{n} \approx -q n(0) \times t_{inv}$$

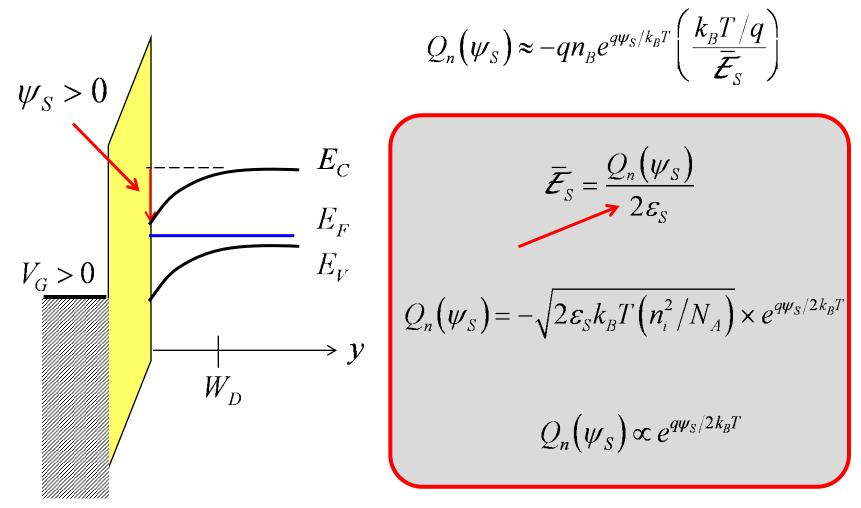
Mobile sheet charge (per cm²)



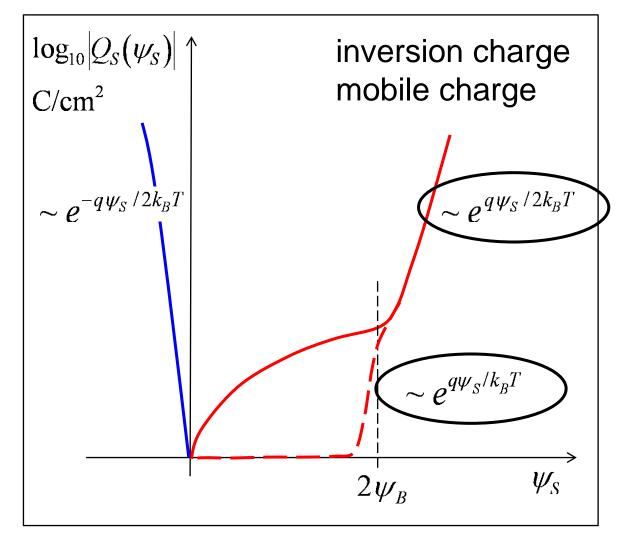
Mobile sheet charge: below threshold



Mobile sheet charge: above threshold



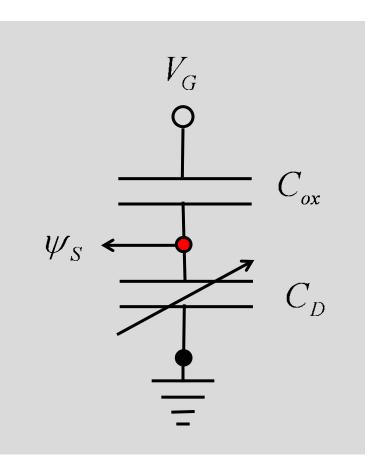
Mobile charge vs. surface potential



$$\psi_{S} = \frac{V_{G}}{m}$$
$$m = 1 + C_{D} / C_{ox}$$

(See Lecture 2.3 slide 11)

$$Q_n(\psi_S) = -qn_B e^{q\psi_S/k_BT} \left(\frac{k_BT/q}{\mathcal{E}_S}\right)$$



$$\mathcal{E}_{S} = \frac{qN_{A}W_{D}}{\varepsilon_{S}} = \frac{qN_{A}}{C_{D}} \qquad C_{D} = \frac{\varepsilon_{S}}{W_{D}}$$

$$m = 1 + C_{D} / C_{ox} \qquad (m-1)C_{ox} = C_{D}$$

$$\mathcal{E}_{S} = \frac{qN_{A}}{(m-1)C_{ox}}$$

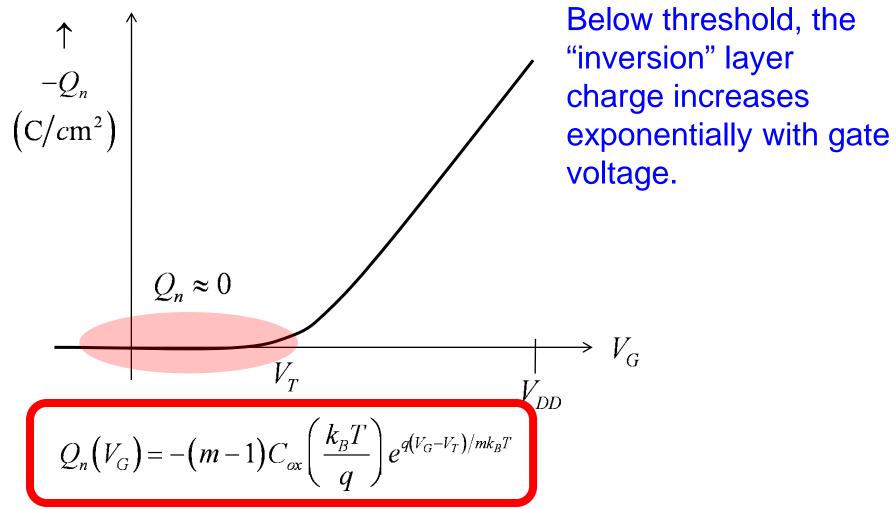
$$Q_{n}(\psi_{S}) = -qn_{B}e^{q\psi_{S}/k_{B}T}\left(\frac{k_{B}T/q}{\mathcal{E}_{S}}\right)$$

$$\psi_{S} = \frac{V_{G}}{m} \qquad m = 1 + C_{D}/C_{ox}$$

$$\mathcal{E}_{S} = \frac{qN_{A}}{(m-1)C_{ox}} \qquad n_{B} = n_{i}^{2}/N_{A}$$

$$\left(\frac{n_{i}}{N_{A}}\right)^{2} = e^{-qV_{T}/mk_{B}T}$$

$$Q_{n}(\psi_{S}) = -(m-1)C_{ox}\left(\frac{n_{i}}{N_{A}}\right)^{2}e^{qV_{GS}/mk_{B}T}\left(\frac{k_{B}T}{q}\right)$$

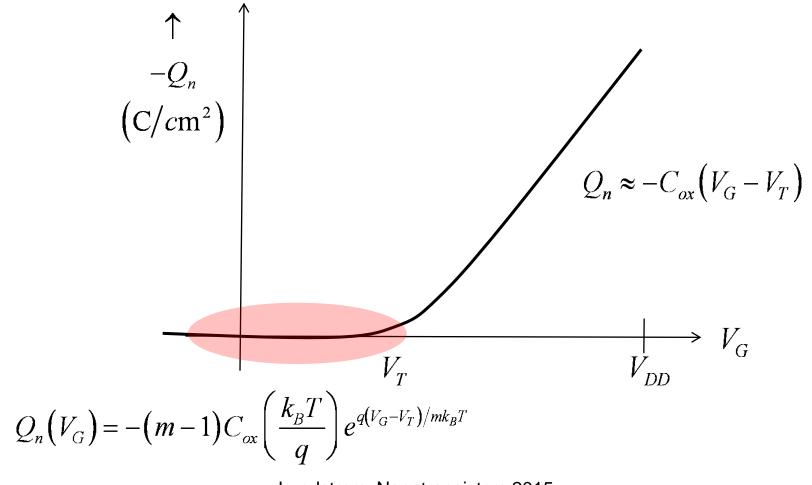


$$V_G = V_{FB} - \frac{Q_S(\psi_S)}{C_{ox}} + \psi_S \qquad V_G = V_{FB} - \frac{Q_D(\psi_S)}{C_{ox}} - \frac{Q_n(\psi_S)}{C_{ox}} + \psi_S$$

$$V_T = V_{FB} - \frac{Q_D(2\psi_B)}{C_{ox}} + 2\psi_B$$

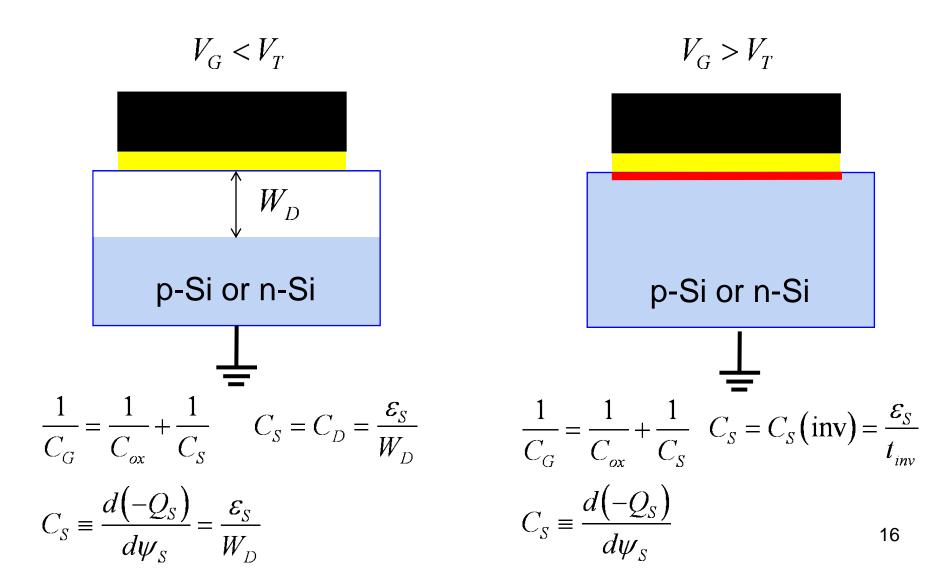
$$V_{G} = V_{FB} - \frac{Q_{D} \left(2\psi_{B} + \delta\psi_{S}\right)}{C_{ox}} - \frac{Q_{n} \left(2\psi_{B} + \delta\psi_{S}\right)}{C_{ox}} + 2\psi_{B} + \delta\psi_{S}$$
$$V_{G} - V_{T} \approx -\frac{Q_{n}}{C_{ox}}$$
$$Q_{n} \approx -C_{ox} \left(V_{G} - V_{T}\right)$$

Mobile charge vs. gate voltage

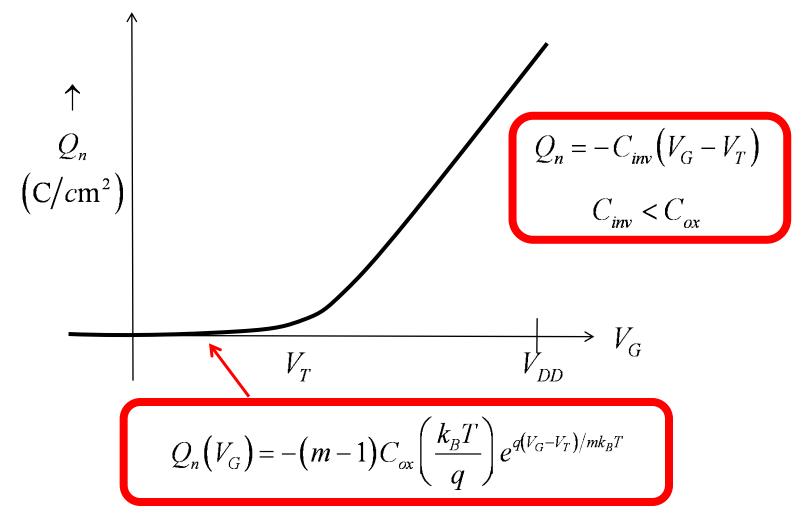


Lundstrom: Nanotransistors 2015

Gate capacitance



Mobile charge vs. gate voltage



Example

On-current conditions: $Q_n = -q \times 10^{13} \text{ C/cm}^2$

Oxide thickness:
$$t_{ox} = 1 \text{ nm} = 10^{-7} \text{ cm}$$
 $\mathcal{K}_{ox} = 3.9$

$$C_{ox} = \frac{\varepsilon_{ox}}{t_{ox}} = 3.45 \times 10^{-6} \text{ F/cm}^2 \qquad C_S(\text{inv}) = \frac{-Q_n}{2(k_B T/q)} = 30.8 \times 10^{-6} \text{ F/cm}^2$$
$$\frac{1}{C_G(\text{inv})} = \frac{1}{C_{ox}} + \frac{1}{C_S(\text{inv})}$$
$$= \frac{1}{3.45 \times 10^{-6}} + \frac{1}{30.8 \times 10^{-6}} \qquad C_G(\text{inv}) = 3.10 \times 10^{-6} \text{ F/cm}^2$$
$$= 0.90C_{ox}$$

CET

$$\frac{1}{C_G} = \frac{1}{C_S(\text{inv})} + \frac{1}{C_{ox}}$$

$$C_G = \frac{C_{ox}C_S(\text{inv})}{C_{ox} + C_S(\text{inv})} < C_{ox}$$

$$C_G \equiv \frac{\kappa_{ox} \varepsilon_0}{CET}$$

Why is it hard to bend the bands more than $2\psi_B$?

below threshold:

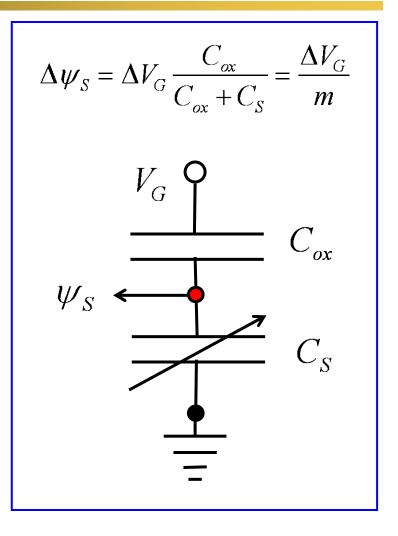
$$C_{S} = \frac{d(-Q_{D})}{d\psi_{S}} = C_{D} = \frac{\varepsilon_{S}}{W_{D}} \approx C_{ox}$$

 $m \approx 1$

above threshold:

$$C_{S} = \frac{d(-Q_{n})}{d\psi_{S}} = C_{S}(\text{inv}) = \frac{\varepsilon_{S}}{t_{inv}} >> C_{o}$$

$$m >> 1$$



Mobile charge vs. gate voltage

$$V_G \ll V_T :$$

$$Q_n(V_G) = -(m-1)C_{ox}\left(\frac{k_BT}{q}\right)e^{q(V_G - V_T)/mk_BT}$$

$$V_G \gg V_T :$$

$$Q_n = -C_{inv}\left(V_G - V_T\right) \qquad C_{inv} \ll C_{ox}$$

Is there a single expression that works both below and above threshold?

Yes – a numerical one – the "surface potential model" Yes – an empirical one – with some fitting parameters

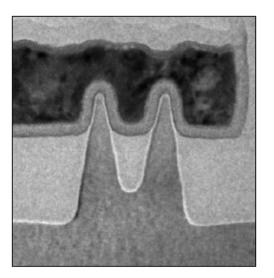
Next lecture

For bulk MOSFETs, we now understand how the mobile charge varies with surface potential and with gate voltage – both above threshold and below.

What happens for modern (fully depleted) structures?

	S	NiSi Poly Si	S	
Source NiSi	Spacer	Gate	Spacer	Drain NiSi
RSD	SDE	Oxide SOI	SDE	RSD
bottom oxide (BOX)				
silicon				

(ETSOI: Source: IBM, 2009)



(FinFET: Source: Intel, 2015)